Simulations and Performance Studies of a MAPS in 65 nm CMOS Imaging Technology

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HSTD13

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Vancouver, Canada



The Tangerine Project

Towards Next Generation Silicon Detectors



Develop the next generation of silicon pixel sensors using novel technologies:

- ★ Vertex detector for future lepton colliders
- ★ Reference detector at DESY-II test beam



Performance parameters:

- ★ Material budget: ≤ 50 µm silicon
- **★** Spatial resolution: $\leq 3 \, \mu m$
- ★ Time resolution: ~ ns

Monolithic Active Pixel Sensor (MAPS)

Science moving to CMOS commercial foundries Advantages & Disadvantages:

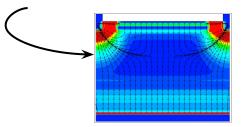
- ★ Profit from state-of-the-art technology
- ★ Reduce costs in large-scale production
- ★ Limited access to manufacturing process information

Introduction & Motivation

Developing a new detector:



- ★ Sensor Simulations: predict sensor behaviour and test designs
 - Electric field distribution in sensor highly dependent on doping concentration and doping profiles
 - MAPS with a small collection electrode have highly complex electric fields

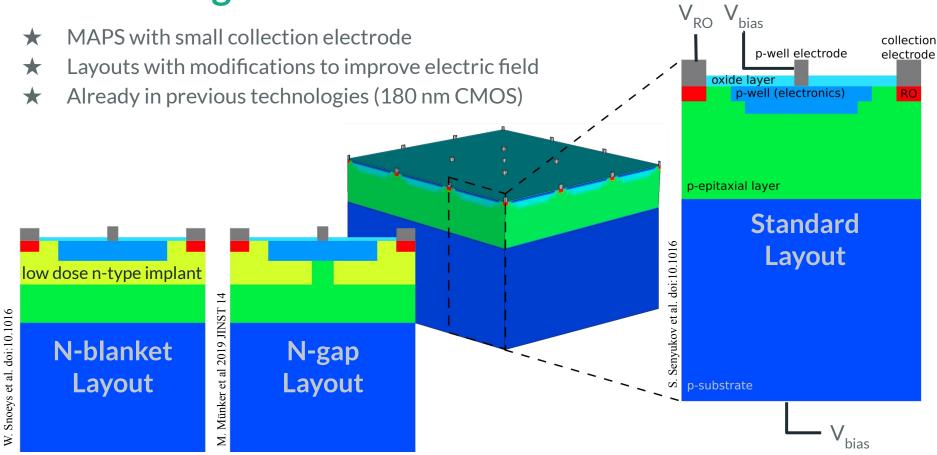


- Simulations based on <u>fundamental principles</u> of silicon detectors and using <u>generic doping profiles</u>
- ★ **Prototype Testing**: characterize sensor under realistic conditions
 - Laboratory
 - Test-beams Part II
- ★ Comparison of simulations with experimental data



Sensor Design

MAPS with small collection electrode



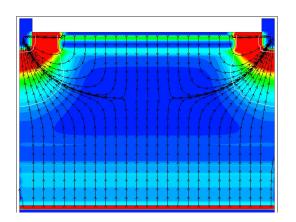
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Part I: Sensor Simulations

Sensor Simulation



- ★ Model sensor volume
- ★ Electric Fields: accurate and realistic
- ★ Observe sensor physical behaviour

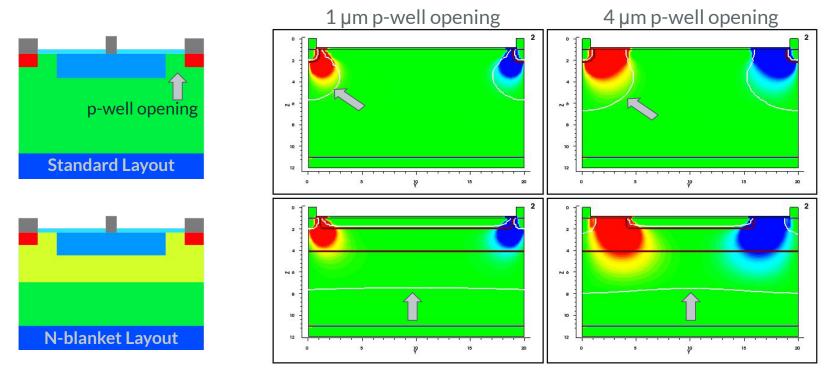


To take into account:

- ★ Avoid abrupt changes in electric field →
 diffusion in doping concentrations at interfaces
- ★ Minimize depleted volume inside p-well → must
 shield electronics from active sensor area
- ★ Charge carriers generated in sensor volume have to reach collection electrode
- ★ No conduction between different biased
 structures → avoid punch-through
- ★ Respect limitations on the operating voltages of transistors in readout electronics

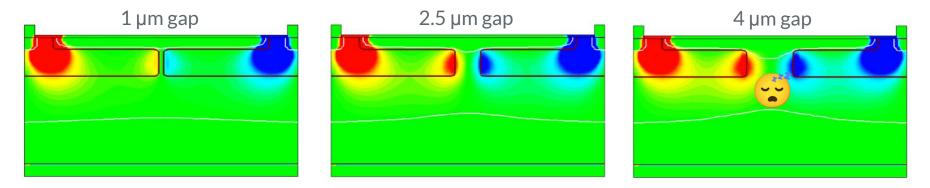
TCAD Simulations - Scans

- ★ Understand effect of design changes: p-well opening width
 - Impact on depleted volume (white line) and lateral electric field (red and blue regions)
 - Less significant for n-blanket layout



TCAD Simulations - Scans

- ★ Optimize design and operation: n-gap size
 - Impact on lateral electric field (red and blue regions)
 - Compromise between strength of lateral electric field and position
 - Also constrained by layout rules of foundry process

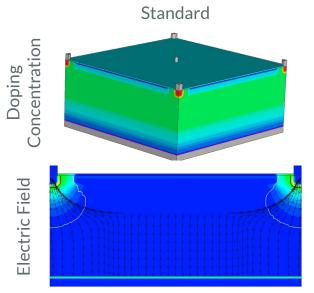


- ★ Finally, select parameters that reproduce expected physical behaviour (similar to previous studies)
- ★ Reminder: simulations based on <u>fundamental principles</u> of silicon detectors and using <u>generic doping profiles</u>

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N-gap Layout

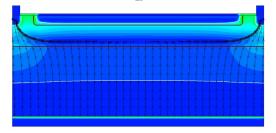
TCAD Simulations - "Final" Result



small depleted volume ↓

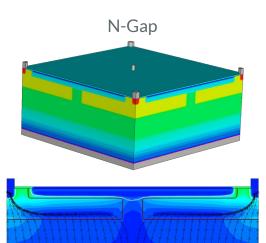
- low efficiency
- high charge sharing between pixels

N-Blanket



larger depleted volume ↓

- improvement in efficiency
- impairment of resolution



higher electric field in pixel corners

- improvement in efficiency and charge collection
- impairment of resolution

Part II: Performance Studies in Test-Beam

Prototypes

- EP R&D
- ★ International collaboration for common submissions to foundry with 65 nm CMOS imaging process, coordinated by CERN
- ★ To date: two foundry submissions with several types of structures and designs

MLR1 (2021) Multi-Layer Reticle

 10 µm OPAMP
 SFAC
 DPTS
 Yonsel

 IPHC
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 25 µm SF
 SFAC
 DPTS
 NikhEf

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 NikhEf

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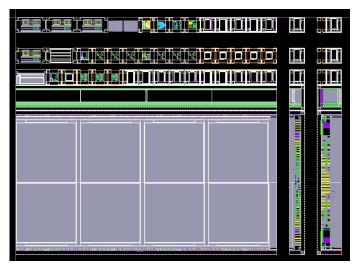
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ER1 (2023) Engineering Run



Prototypes MLR1 (2021)

ER1 (2023)



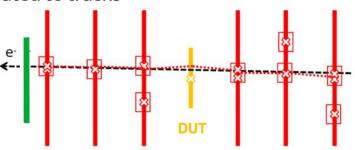
Prototypes MLR1 (2021)

ER1 (2023)

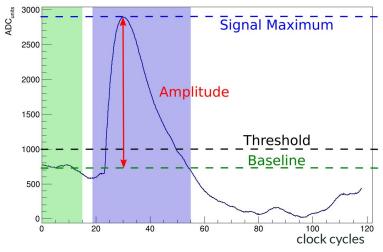


Test-Beam Setup

- ★ DESY II Test Beam Facility with 4 GeV electron beam <u>J. Drevling-Eschweiler et al.</u>
- ★ MIMOSA26 Telescope H. Jansen et al.
- ★ Trigger plane with configurable ROI: TelePix (see <u>L. Huth's talk</u>)
- ★ DUT (Device Under Test): APTS
- ★ DAQ system based on Caribou (see <u>F. Feindt's talk</u>)
- ★ Corryvreckan framework (see <u>L. Huth's talk</u>) for track <u>D. Dannheim et al.</u> reconstruction and data analysis
- ★ Events defined as waveforms in DUT above threshold associated to tracks





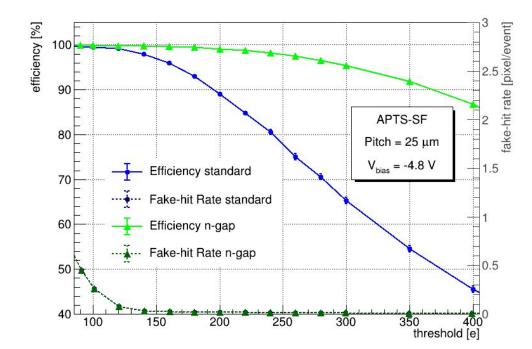


Test-Beam Results - Efficiency

- ★ Comparison of **standard** and **n-gap** designs
- \star Efficiency reduced with higher thresholds

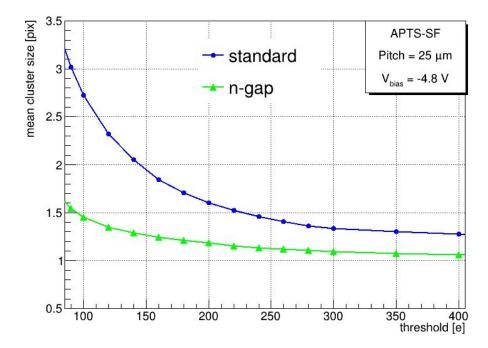
sharing

★ Higher overall efficiency for n-gap \rightarrow larger depleted volume and reduced charge



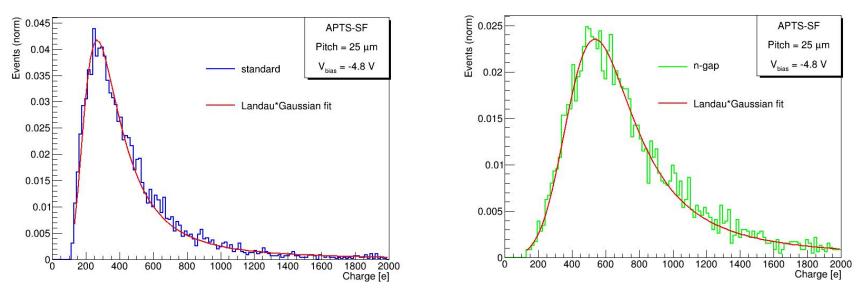
Test-Beam Results - Cluster Size

- ★ Cluster size reduced with higher thresholds
- ★ Higher overall cluster size for standard \rightarrow more charge sharing



Test-Beam Results - Charge Distribution Seed Pixel

- ★ ADC units converted to electrons by x-ray fluorescence calibration
- ★ Landau^{*}Gaussian Distribution \rightarrow expected for thin sensors
 - \circ MPV standard: 264 e ± 2 e
 - MPV n-gap: $496 e \pm 4 e$
- ★ More charge collected for n-gap \rightarrow larger depleted volume



Part III: Simulation vs. Experimental Data

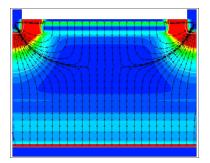
Combination of Simulation Tools



Silicon to Software

Technology Computer-Aided Design

- Model sensor volume
- Electric Fields: accurate and realistic

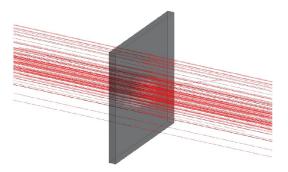


- Show sensor physical behaviour in Part I
- Obtain electric fields to input in Monte Carlo simulations



Allpix²: Monte Carlo Simulations for Semiconductor Detectors https://doi.org/10.1016/j.nima.2018.06.020

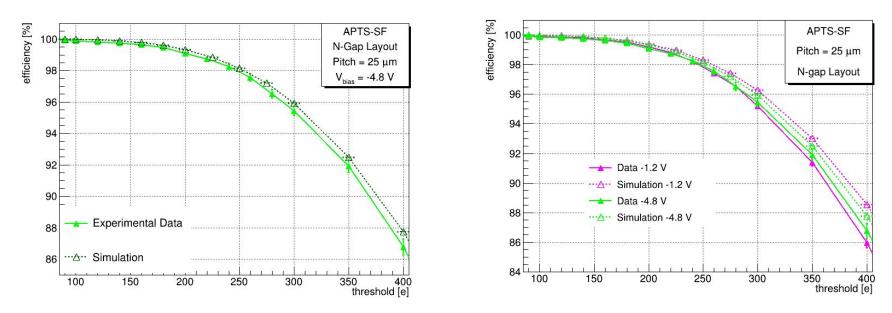
- Simulate full response of detector
- Particle Events: fast and high statistics



Obtain performance parameters Compare to data in **Part III**

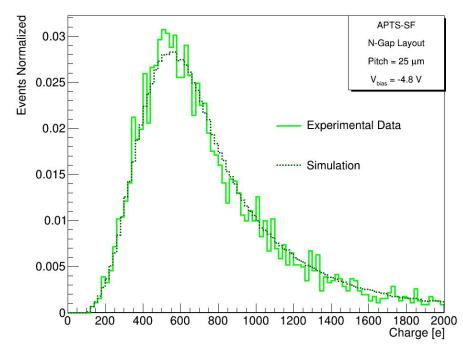
Simulation vs. Experimental Data - Efficiency

- ★ N-gap design
- ★ Experimental data compatible with simulations
- **\star** Negligible changes at different bias voltages \rightarrow similar trend for simulations
- **\star** Error bars not final \rightarrow only statistical uncertainties



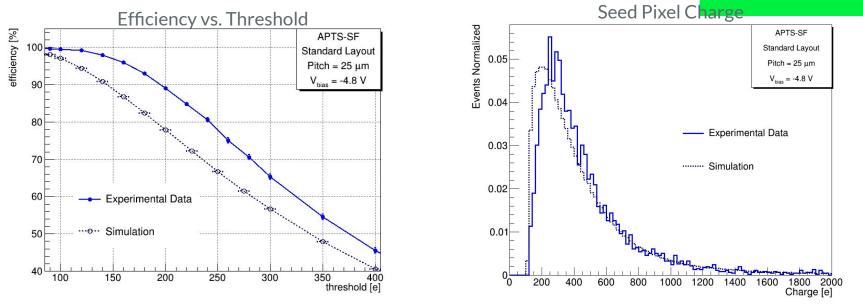
Simulation vs. Experimental Data - Charge Distribution

- ★ N-gap design
- \star Charge distribution of the seed pixel
- \star Experimental data compatible with simulations



Simulation vs. Experimental Data - Outlook

- **Standard** design \rightarrow diffusion dominated \rightarrow more sensitive to some parameters
- ★ Most performance values still don't match, but...
- ★ Gives hints on which parameters should be adjusted in simulations
 - Substrate and/or epitaxial layer doping concentration
 - Retracted deep p-well

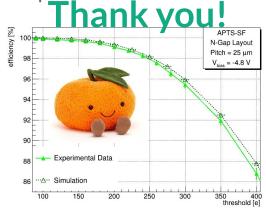


Summary & Conclusions

- ★ Simulation approach using generic doping profiles and semiconductor principles
- ★ Combination of TCAD + Monte Carlo simulation
 - Provided very useful insights for future sensor optimization
 - Produced results comparable with measurements
- ★ Beam test of Analog Pixel Test Structure (APTS)
 - Compared performance of standard and n-gap designs
- ★ Some simulations and experimental results follow a similar trend
- ★ Some mismatch provides important feedback for simulation improvements

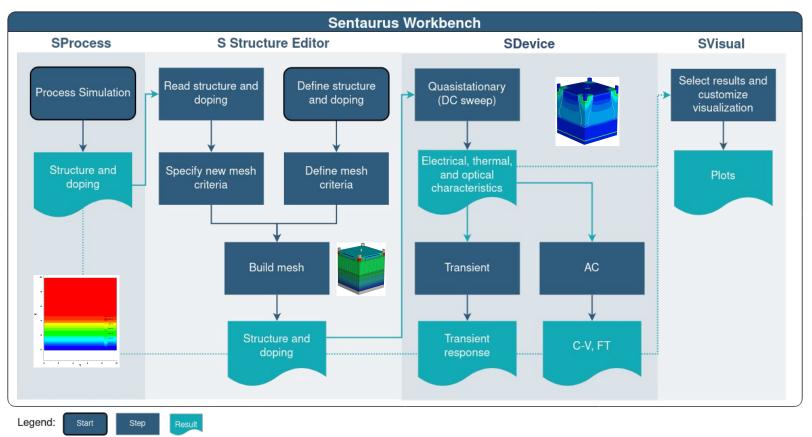
Outlook

- ★ More simulations on relevant parameters
- ★ Add uncertainties on simulation results
- ★ More measurements \rightarrow more statistics
- ★ More studies, including spatial resolution and timing



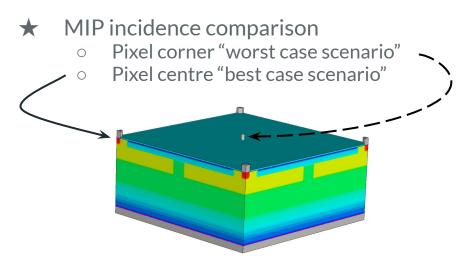
Back-up

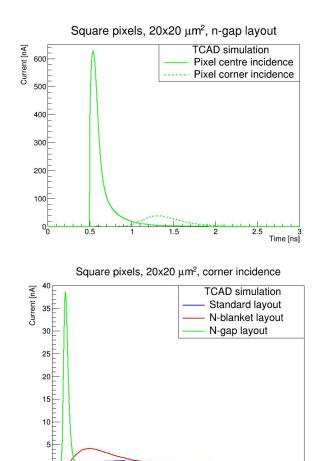
TCAD Simulation Workflow Example



TCAD - Transient Simulations

Time-dependent induced signal by MIP





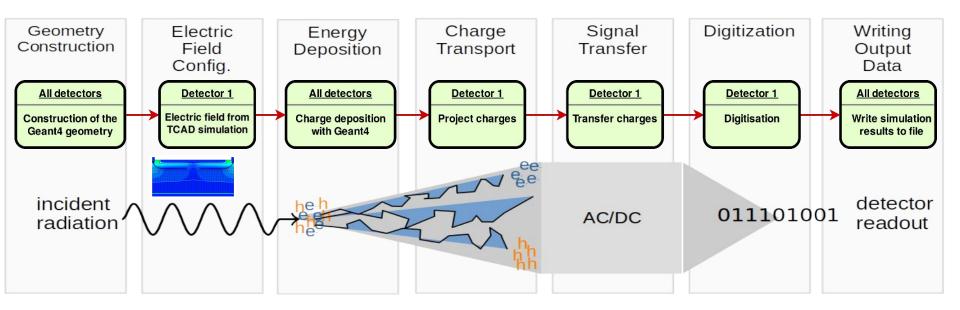
★ Layout comparison

• Improvements brought on by modifications

20

25 Time [ns]

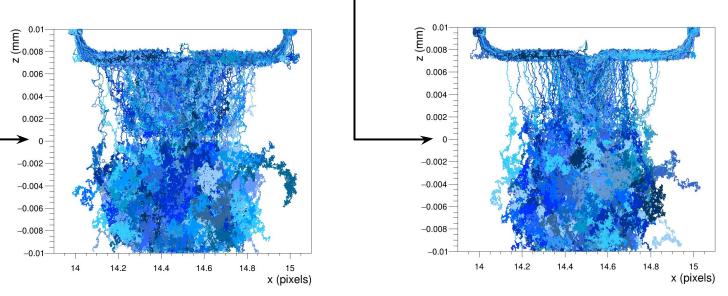
Monte Carlo Simulation Workflow Example



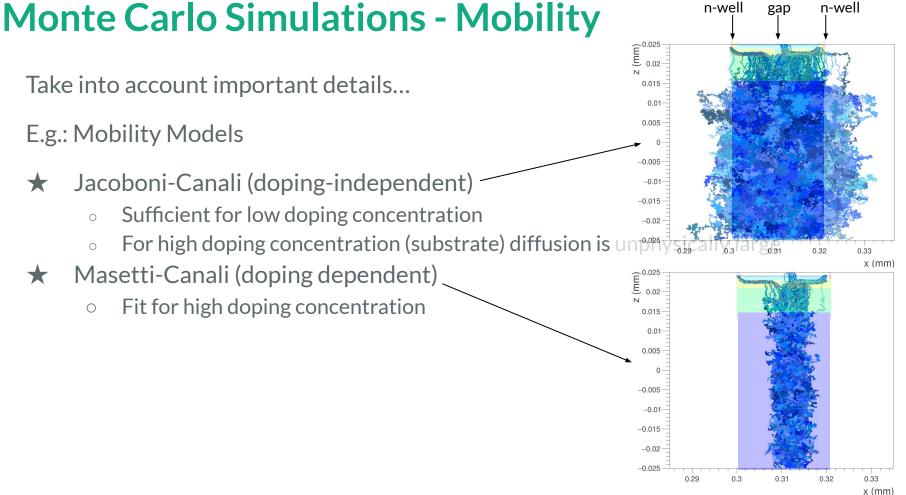
Monte Carlo Simulations - Diffusion

Comparing effect of electric field between substrate and epitaxial layer

- Without dopant diffusion: significant electric field in interface region
 Unphysical
- ★ With dopant diffusion: smooth transition region



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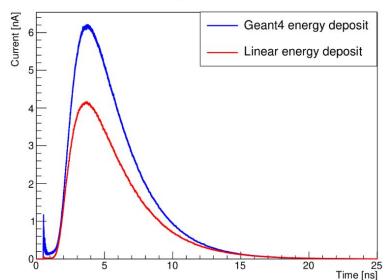


Monte Carlo Simulations - Energy Deposition

Transient simulations comparing:

- ★ Linear energy deposition (TCAD)
 - Generates 63 electron-hole pairs per μ m \rightarrow most probable value
- **\star** Geant4 (Allpix²)
 - O Includes stochastic effects → takes into account all values from energy deposition distribution

Each signal is the average of 10 000 events, incident in the pixel corner



N-blanket layout, corner incidence

Monte Carlo vs. TCAD - Transient

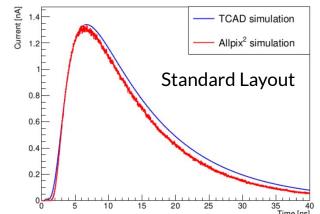
Electrostatic potentials from TCAD can be used to generate weighting potentials

 \rightarrow Perform **transient simulations** with Allpix²

- ★ Lower computational cost
- ★ Reproduce many events
- ★ Allows use of Geant4 energy deposition (see next slide)

Comparison Allpix² vs. TCAD:

- ★ Same settings for charge carrier creation and mobility
- \star Results in general agreement

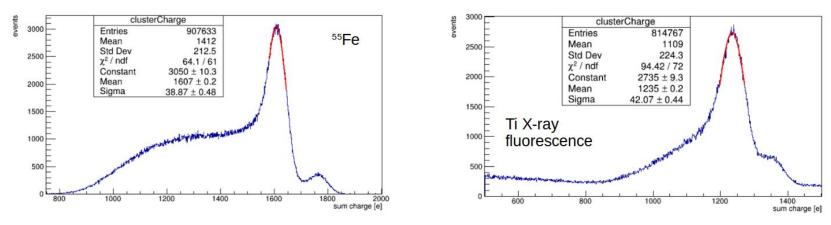


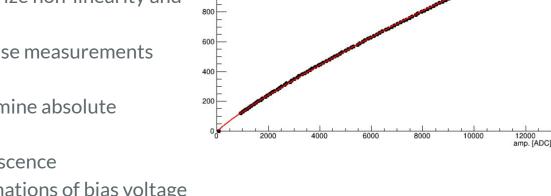
APTS Operational Parameters

- ★ Samples: 19 (AF25), 24 (AF25B), 29 (AF25P)
- ★ Pitch: 25 µm
- ★ Type: standard, n-blanket and n-gap
- ★ Split: 4
- ★ Vsub = Vpwell = -1.2 V, -2.4 V, -3.6 V, -4.8 V (,-5.2 V only for sample 19)
- ★ Ireset = $1 \mu A$
- ★ Ibiasn = 20 μA
- **★** Ibiasp = $2 \mu A$
- ★ Ibias4 = 546 µA
- ★ Ibias3 = 200 μA
- ★ Vreset = 0.5 V

Calibration

- ★ Test pulse measurements to characterize non-linearity and pixel-to-pixel variations
- ★ Apply inverse gain curve from test pulse measurements (per pixel)
- ★ Perform ⁵⁵Fe measurements to determine absolute calibration factor
- ★ Check calibration with Ti X-ray fluorescence
- ★ Calibration for all samples and combinations of bias voltage





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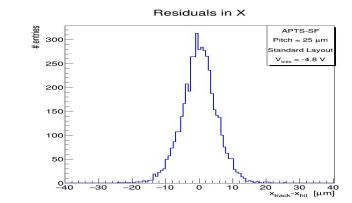
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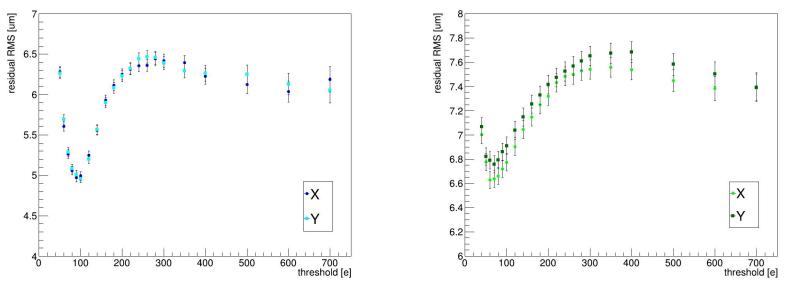
Spatial Residuals

★ Smaller residuals RMS for standard layout
 → better spatial resolution expected

Residuals RMS vs. Threshold

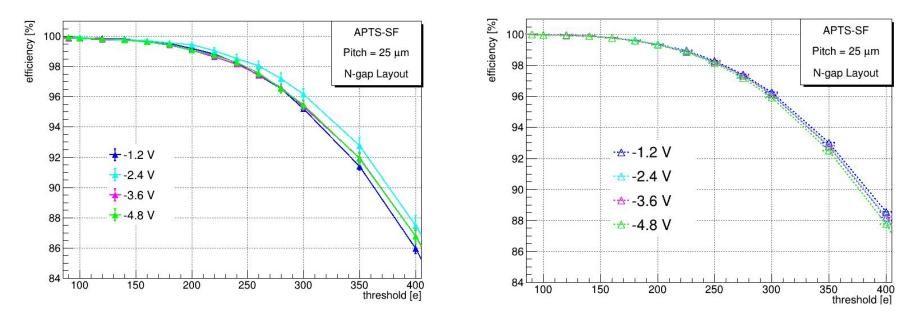


Residuals RMS vs. Threshold



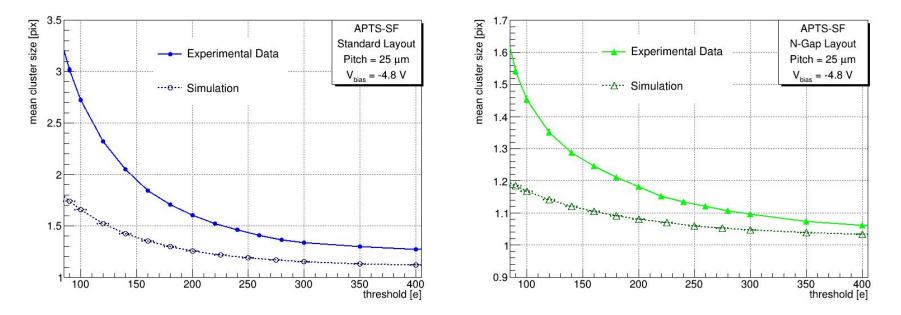
Simulation vs. Experimental Data - Efficiency

- ★ Experimental data compatible with simulations
- ★ Similar trend for different bias voltages



Simulation vs. Experimental Data - Cluster Size

- \star Cluster size mismatch
- ★ Gives hints on which parameters should be adjusted in simulations
 - Substrate doping concentration



Time-dependent Alignment

- ★ During test-beam, DUT experienced a physical displacement over time due to temperature changes
- ★ Offline time-dependent alignment using Corryvreckan

